

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L18	1	"20020162827".pn.	US-PGPUB; USPAT	OR	ON	2009/01/16 22:26
L19	59	ratio same earth same area same wall	US-PGPUB; USPAT	OR	ON	2009/01/16 22:44
L20	14	19 and plasma	US-PGPUB; USPAT	OR	ON	2009/01/16 22:45
L22	59	earth with wall with inner with chamber	US-PGPUB; USPAT	OR	ON	2009/01/16 23:18
L23	29	22 and plasma	US-PGPUB; USPAT	OR	ON	2009/01/16 23:18
L25	4	earth same (wall with inner with chamber) same chip\$4	US-PGPUB; USPAT	OR	ON	2009/01/16 23:22
L26	3192	(dummy near2 substrate)	US-PGPUB; USPAT	OR	ON	2009/01/16 23:59
L27	6263	(clean\$3 or etch\$3 or treat \$3 or remov\$3) same (apparatus or chamber) same plasma same ("al" or aluminium or aluminum)	US-PGPUB; USPAT	OR	ON	2009/01/16 23:59
L28	44	L27 and L26	US-PGPUB; USPAT	OR	ON	2009/01/16 23:59
L29	8	L28 and 134/1-1.3.ccls.	US-PGPUB; USPAT	OR	ON	2009/01/16 23:59
L37	1053	shirayone-shigeru.in. ono- tetsuo.in. itabashi-naoshi. in. yoshigai-motohiko.in. abe-takahiro.in. shimomura-takahiro.in. kitsunai-hiroyuki.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/17 00:29
L38	7	37 and ((clean\$3 or etch \$3 or treat\$3 or remov\$3) same (apparatus or chamber) same plasma same (wafer or substrate or semiconductor)) and (("hbr" or hydrobromic or "hydrogen bromide") same ("cl.sub.2" or chlorine)) and ((aluminum or aluminium or "al") with (fluoride or fluorine))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/17 00:29

L39	732	"hitachi high-technologies corporation".as.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/17 00:30
L40	1	39 and ((clean\$3 or etch\$3 or treat\$3 or remov\$3) same (apparatus or chamber) same plasma same (wafer or substrate or semiconductor)) and (("hbr" or hydrobromic or "hydrogen bromide") same ("cl.sub.2" or chlorine)) and ((aluminum or aluminium or "al") with (fluoride or fluorine))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/17 00:31
S1	1070	(clean\$3 or etch\$3 or treat\$3 or remov\$3) same (apparatus or chamber) same ("hbr" or hydrobromic or "hydrogen bromide") same ("cl.sub.2" or chlorine)	US-PGPUB; USPAT	OR	ON	2009/01/15 17:05
S2	3192	(dummy near2 substrate)	US-PGPUB; USPAT	OR	ON	2009/01/15 17:05
S3	13	S1 and S2	US-PGPUB; USPAT	OR	ON	2009/01/15 17:05
S4	13	S3 and plasma	US-PGPUB; USPAT	OR	ON	2009/01/15 17:05
S5	3	S4 and "134".clas.	US-PGPUB; USPAT	OR	ON	2009/01/15 17:05
S6	82	S1 same ("al" or aluminium or aluminum)	US-PGPUB; USPAT	OR	ON	2009/01/15 17:09
S7	43	S6 same plasma	US-PGPUB; USPAT	OR	ON	2009/01/15 17:09
S8	1	S7 and S2	US-PGPUB; USPAT	OR	ON	2009/01/15 17:09
S9	6263	(clean\$3 or etch\$3 or treat\$3 or remov\$3) same (apparatus or chamber) same plasma same ("al" or aluminium or aluminum)	US-PGPUB; USPAT	OR	ON	2009/01/15 17:10
S10	44	S9 and S2	US-PGPUB; USPAT	OR	ON	2009/01/15 17:10
S11	9	S10 and "134".clas.	US-PGPUB; USPAT	OR	ON	2009/01/15 17:10

S12	70	(clean\$3 or etch\$3 or treat\$3 or remov\$3) same (apparatus or chamber) same ("hbr" or hydrobromic or "hydrogen bromide") same ("cl. sub.2" or chlorine)	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/15 17:16
S13	1	S12 and plasma and (dummy near2 substrate)	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/15 17:16
S14	970	(clean\$3 or etch\$3 or treat\$3 or remov\$3) same (apparatus or chamber) same plasma same ("al" or aluminium or aluminum)	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/15 17:17
S15	1	S14 and plasma and (dummy near2 substrate)	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/15 17:17
S16	1	"4786352".pn.	US-PGPUB; USPAT	OR	ON	2009/01/15 17:26
S17	1	"6186153".pn.	US-PGPUB; USPAT	OR	ON	2009/01/15 17:34
S18	1	"20050072444".pn.	US-PGPUB; USPAT	OR	ON	2009/01/15 17:58
S19	1	"4786352".pn.	US-PGPUB; USPAT	OR	ON	2009/01/15 19:00
S20	628	(clean\$3 or etch\$3 or treat\$3 or remov\$3) same (apparatus or chamber) same ("hbr" or hydrobromic or "hydrogen bromide") same ("cl. sub.2" or chlorine) same plasma	US-PGPUB; USPAT	OR	ON	2009/01/15 19:04
S21	36	S20 and "134".clas.	US-PGPUB; USPAT	OR	ON	2009/01/15 19:04
S22	1070	(clean\$3 or etch\$3 or treat\$3 or remov\$3) same (apparatus or chamber) same ("hbr" or hydrobromic or "hydrogen bromide") same ("cl. sub.2" or chlorine)	US-PGPUB; USPAT	OR	ON	2009/01/15 19:05
S23	82	S22 same ("al" or aluminium or aluminum)	US-PGPUB; USPAT	OR	ON	2009/01/15 19:05
S24	43	S23 same plasma	US-PGPUB; USPAT	OR	ON	2009/01/15 19:05

S25	70	(clean\$3 or etch\$3 or treat\$3 or remov\$3) same (apparatus or chamber) same ("hbr" or hydrobromic or "hydrogen bromide") same ("cl. sub.2" or chlorine)	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/15 19:12
S26	5	S25 same ("al" or aluminium or aluminum)	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/15 19:12
S27	31	(clean\$3 or etch\$3 or treat\$3 or remov\$3) same (apparatus or chamber) same ("hbr" or hydrobromic or "hydrogen bromide") same ("n. sub.2" or nitrogen or "co" or "carbon monoxide" or "co.sub.2" or "carbon dioxide" or "h.sub.2" or hydorgen or "so.sub.2" or "sulfur dioxide")	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/15 19:16
S28	19	S27 and plasma	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/15 19:17
S29	393	((clean\$3 or etch\$3 or treat\$3 or remov\$3) same (apparatus or chamber) same ("al" or aluminium or aluminum) same plasma) and (("hbr" or hydrobromic or "hydrogen bromide") same ("cl. sub.2" or chlorine) same (gas or plasma))	US-PGPUB; USPAT	OR	ON	2009/01/16 00:33
S30	38	S29 and "134".clas.	US-PGPUB; USPAT	OR	ON	2009/01/16 00:34
S34	210	((clean\$3 or etch\$3 or treat\$3 or remov\$3) same (apparatus or chamber) same ("al" or aluminium or aluminum) same plasma) and (("hbr" or hydrobromic or "hydrogen bromide") same ("cl. sub.2" or chlorine) same ("n.sub.2" or nitrogen or "co" or "carbon monoxide" or "co.sub.2" or "carbon dioxide" or "h. sub.2" or hydorgen or "so.	US-PGPUB; USPAT	OR	ON	2009/01/16 00:47

		sub.2" or "sulfur dioxide" or inert))				
S35	23	S34 and "134".clas.	US-PGPUB; USPAT	OR	ON	2009/01/16 00:47
S37	5	((clean\$3 or etch\$3 or treat\$3 or remov\$3) same (apparatus or chamber) same (residu\$3 or contaminat\$5 or particle) same plasma) and (("hbr" or hydrobromic or "hydrogen bromide") same ("cl.sub.2" or chlorine) same ("n.sub.2" or nitrogen or "co" or "carbon monoxide" or "co.sub.2" or "carbon dioxide" or "h.sub.2" or hydorgen or "so.sub.2" or "sulfur dioxide" or inert))	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/16 00:49
S38	265	((clean\$3 or etch\$3 or treat\$3 or remov\$3) same (apparatus or chamber) same (residu\$3 or contaminat\$5 or particle) same plasma) and (("hbr" or hydrobromic or "hydrogen bromide") same ("cl.sub.2" or chlorine) same ("n.sub.2" or nitrogen or "co" or "carbon monoxide" or "co.sub.2" or "carbon dioxide" or "h.sub.2" or hydorgen or "so.sub.2" or "sulfur dioxide" or inert))	US-PGPUB; USPAT	OR	ON	2009/01/16 00:50
S39	37	S38 and "134".clas.	US-PGPUB; USPAT	OR	ON	2009/01/16 00:50
S40	20	S39 and @pd<"20040304"	US-PGPUB; USPAT	OR	ON	2009/01/16 00:51
S41	23	("4376672" "5298790" "5423941" "5585012" "5756400" "5814563"). PN. OR ("6318384"). URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2009/01/16 14:10

S43	2	S41 and (("hbr" or hydrobromic or "hydrogen bromide") same ("cl. sub.2" or chlorine) same ("n.sub.2" or nitrogen or "co" or "carbon monoxide" or "co.sub.2" or "carbon dioxide" or "h. sub.2" or hydorgen or "so. sub.2" or "sulfur dioxide" or inert))	US-PGPUB; USPAT; USOCR	OR	ON	2009/01/16 14:11
S44	1	"6136211".pn.	US-PGPUB; USPAT; USOCR	OR	ON	2009/01/16 14:37
S48	3	((clean\$3 or etch\$3 or treat\$3 or remov\$3) same (apparatus or chamber) same (residu\$3 or contaminat\$5 or particle) same plasma) and ("sicl. sub.4" or Tetrachlorosilane)	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/01/16 15:06
S49	396	((clean\$3 or etch\$3 or treat\$3 or remov\$3) same (apparatus or chamber) same (residu\$3 or contaminat\$5 or particle) same plasma) and ("sicl. sub.4" or Tetrachlorosilane)	US-PGPUB; USPAT	OR	ON	2009/01/16 15:07
S50	42	S49 and "134".clas.	US-PGPUB; USPAT	OR	ON	2009/01/16 15:08

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